

VLSI Week 1

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Contents

1	P and N Type Silicon	2
2	Diode Design	2
3	Transistor Design	2
4	Transistor Level Design of Digital Components	2
4.1	Inverter	2
4.2	NAND	2
4.3	NOR	2
4.4	Multi Input NAND	2
4.5	TriState Buffers	2
4.6	Multiplexers	2
4.7	Latches	2
4.8	Flip Flops	2
5	Physical Layout Level Design	2
6	Fabrication Process	2

1 P and N Type Silicon

P type silicon involves doping the neutral silicon with negatively charged atoms, the introduced atoms require an electron from one of the surrounding silicon atoms. This makes the silicon atom positively charged, creating a mobile positive charge, these are referred to as "holes". Holes move around through stealing their electron from surrounding silicon atoms.

The alternative type of doping is referred to as N-type, in which a negatively charged atom is doped in the silicon, this causes one of the surrounding silicon atoms to accept an additional electron, and become negatively charged. This electron can then be passed around the silicon substrate in order to create charge flow.

2 Diode Design

3 Transistor Design

4 Transistor Level Design of Digital Components

4.1 Inverter

4.2 NAND

4.3 NOR

4.4 Multi Input NAND

4.5 TriState Buffers

4.6 Multiplexers

4.7 Latches

4.8 Flip Flops

5 Physical Layout Level Design

6 Fabrication Process